In the Claims:

- 1. (Previously Presented) An electronic component comprising:
 - a wafer;
 - a plurality of bond pads disposed on a surface of the wafer;

a plurality of functional 3-D structures disposed on the surface of the wafer, such that each bond pad is laterally spaced from the plurality of bond pads so that each bond pad is associated with a laterally-spaced one of the 3-D structures, each functional 3-D structure including a non-conductive compliant base element and having an upper surface spaced from the surface of the wafer;

a plurality of reroute traces, each reroute trace extending over the surface of the wafer between a bond pad and its associated 3-D structure such that each reroute trace is electrically connected to one of the bond pads and extends onto the upper surface of the associated laterally-spaced one of the functional 3-D structures so that the reroute trace provides an electrical connection between the bond pad and the upper surface of the associated functional 3-D structure; and

a plurality of selected 3-D structures disposed on the surface of the wafer to provide a mechanical reinforcement, wherein at least some of the selected 3-D structures have a greater mechanical load-bearing capacity than some of the functional 3-D structures.

2. (Original) The component of claim 1 wherein each reroute trace comprises a copper/nickel layer that is covered by a gold layer.

- 3. (Original) The component of claim 1 wherein the selected 3-D structures have a lower degree of compressibility than the functional 3-D structures.
- 4. (Previously Presented) The component of claim 1 wherein the selected 3-D structures have a greater height than the functional 3-D structures.
- 5. (Previously Presented) The component of claim 1 wherein each of the selected 3-D structures includes a compliant base element that has a greater volume than the compliant base element of the functional 3-D structures.
 - 6-7. (Cancelled)
 - 8. (Original) The component of claim 1 wherein the selected 3-D structures are arranged in a regularly distributed manner in an edge region of the wafer.
 - 9. (Original) The component of claim 1 wherein the selected 3-D structures are arranged in a regularly distributed manner over the wafer.
 - 10. (Original) The component of claim 1 wherein the selected 3-D structures are able to be electrically bonded.
 - 11-33. (Cancelled)
 - 34. (Previously Presented) The electronic component of claim 1, wherein the compliant base element is formed from silicone.

- 35. (Previously Presented) The component of claim 1 wherein each of the selected 3-D structures is protected by a metal cap.
- 36. (Previously Presented) The component of claim 1 wherein each of the selected 3-D structures is surrounded by a metallic supporting ring.
- 37. (New) The component of claim 1 wherein each of the selected 3-D structures have a support structure formed upon a surface of the wafer.
- 38. (New) The component of claim 37 wherein the support structure comprises a metal ring formed along side surfaces of the selected 3-D structures.
- 39. (New) The component of claim 38 wherein the metal ring is not disposed on any portion of an upper surface of the selected 3-D structures.
- 40. (New) The component of claim 37 wherein the support structure is formed from the same material as the reroute traces.
- 41. (New) The component of claim 37 wherein each reroute trace comprises a copper/nickel layer that is covered by a gold layer.
- 42. (New) The component of claim 37 wherein the selected 3-D structures have a lower degree of compressibility than the functional 3-D structures.
- 43. (New) The component of claim 37 wherein the selected 3-D structures have a greater height than the functional 3-D structures.

- 44. (New) The component of claim 37 wherein each of the selected 3-D structures includes a compliant base element that has a greater volume than the compliant base element of the functional 3-D structures.
- 45. (New) The component of claim 37 wherein the selected 3-D structures are arranged in a regularly distributed manner in an edge region of the wafer.
- 46. (New) The component of claim 37 wherein the selected 3-D structures are arranged in a regularly distributed manner over the wafer.